

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently amended) A lithographic apparatus, comprising:  
a radiation system configured to provide a beam of radiation;  
a support ~~structure~~ configured to support a patterning device adapted to impart a desired pattern to the beam of radiation;  
a substrate holder configured to hold a substrate;  
a projection system that projects the patterned beam onto a target portion of the substrate; and  
an actuator configured to position at least one part within the radiation system, the support ~~structure~~, the substrate holder, or the projection system, the actuator comprising a coil arrangement in thermal contact with ~~at least one~~ a cooling element,  
said ~~at least one~~ cooling element being provided with one or more slits configured to increase electrical resistance of eddy current paths.
2. (Original) A lithographic apparatus according to Claim 1, wherein the slits are arranged to be substantially parallel to each other.
3. (Currently amended) A lithographic apparatus according to Claim 1, wherein the slits are arranged to be substantially perpendicular to the direction of ~~[[the]]~~ an induced electric field.
4. (Currently amended) A lithographic apparatus according to Claim 1, wherein the slits are arranged to be substantially parallel to the direction of ~~[[the]]~~ an induced electric field.
5. (Currently amended) A lithographic apparatus according to Claim 1, wherein the slits are arranged to be at an oblique angle, to the direction of ~~[[the]]~~ an induced electric field.
6. (Currently amended) A lithographic apparatus according Claim 1, wherein the slit lengths are limited so as not to extend across ~~[[the]]~~ an entire length of the cooling element.

7. (Original) A lithographic apparatus according to Claim 1, wherein adjacent slits extend from opposite sides of the cooling element.
8. (Currently amended) A lithographic apparatus according to Claim 1, wherein cooling channels are integrated with the slits ~~in such a way as~~ to provide a plurality of parallel paths arranged to reduce flow impedance.
9. (Original) A lithographic apparatus according to Claim 1, wherein cooling channels are arranged in a substantially symmetrical network to provide uniform coverage of the cooling element.
10. (Original) A lithographic apparatus according to Claim 1, wherein the slits are filled to protect from outgassing from the coil.
11. (Currently amended) A device manufacturing method, comprising:
  - ~~providing supporting~~ a substrate ~~held~~ by a substrate holder;
  - providing a beam of radiation using an illumination system;
  - imparting a desired pattern onto the beam of radiation by a patterning device supported by a support ~~structure~~;
  - projecting the patterned beam of radiation onto a target portion of the substrate via a projection system; and
  - positioning at least a part of one of the radiation system, the support ~~structure~~, the substrate holder, and the projection system by an actuator, the actuator comprising a coil arrangement in thermal contact with ~~at least one~~ a cooling element, wherein the cooling element is provided with one or more slits configured to increase electrical resistance of eddy current paths.
12. (Currently amended) A lithographic actuating mechanism, comprising:
  - a magnet assembly;
  - ~~at least one~~ a cooling element; and
  - a coil arrangement in thermal contact with said ~~at least one~~ cooling element;
  - said ~~at least one~~ cooling element being provided with one or more slits configured to increase electrical resistance of eddy current paths.

13. (Original) A lithographic actuating mechanism according to Claim 12, wherein the slits are arranged to be substantially parallel to each other.
14. (Currently amended) A lithographic actuating mechanism according to Claim 12, wherein the slits are arranged to be substantially perpendicular to the direction of ~~[[the]]~~ an induced electric field.
15. (Currently amended) A lithographic actuating mechanism according to Claim 12, wherein the slits are arranged to be substantially parallel to the direction of ~~[[the]]~~ an induced electric field.
16. (Currently amended) A lithographic actuating mechanism according to Claim 12, wherein the slits are arranged to be at an oblique angle, to the direction of ~~[[the]]~~ an induced electric field.
17. (Currently amended) A lithographic actuating mechanism according to Claim 12, wherein the slit lengths are limited so as not to extend across ~~[[the]]~~ an entire length of the cooling element.
18. (Original) A lithographic actuating mechanism according to Claim 12, wherein adjacent slits extend from opposite sides of the cooling element.
19. (Currently amended) A lithographic actuating mechanism according to Claim 12, wherein cooling channels are integrated with the slits ~~in such a way as~~ to provide a plurality of parallel paths arranged to reduce flow impedance.
20. (Original) A lithographic actuating mechanism according to Claim 12, wherein cooling channels are arranged in a substantially symmetrical network to provide uniform coverage of the cooling element.
21. (Original) A lithographic actuating mechanism according to Claim 12, wherein the slits are filled to protect from outgassing from the coil.